

Punch through protection and p-stop ion concentration in HPK strip mini-sensors

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Protection of AC coupling capacitors from beam splashes has been studied on the HPK ATLAS07 mini-sensors with special structures, BZ4A,B,C and D, for p-stop ion concentrations $2e12$, $4e12$ and $1e13$ ion/cm². Punch through voltage was measured by DC methods on both ends of strips and it was found that voltage dominantly depends on ion concentration for all punch through structures. Minimum PT voltage was found for p-stop concentration $2e12$ ion/cm² and the voltage is growing with concentration. IV characteristics have been measured for whole sample of 74 sensors. All sensors with p-stop isolation were successfully operating up to 1000V and sensors with p-stop plus p-spray $2e12$ ion/cm² -up to 920V only. Full depletion voltage deduced from CV characteristics is in the range 180V –290V. An inter-strip capacitance, C_{int} , is constant for bias voltages higher than respective full depletion voltages and C_{int} does not depend on ion concentration within of $\pm 20\%$. First sample of 12 sensors has been irradiated in reactor in Rez near Prague to $4e14$, $2e15$ and $1e16$ neq/cm² and sensors will be investigated soon.

Next study concerns a thermal dependence of poly-silicon bias resistors of non-irradiated and irradiated sensors up to $4E14$ neq/cm². The respective temperature coefficients are -6.7 k Ω /centigrade for non-irradiated sensors and -10.1 k Ω /centigrade for fluency $4e14$ neq/cm².

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